

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Chan, et al.

Serial No.:

09/817,120

Group Art Unit:

2825

Filed:

March 27, 2001

Examiner:

Rocchegiani, Renzo

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For:

METHOD FOR MANUFACTURING DEVICE SUBSTRATE WITH

METAL BACK-GATE AND STRUCTURE FORMED

Honorable Assistant Commissioner of Patents Washington, D.C. 20231

RESPONSE TO FIRST OFFICE ACTION AND RESTRICTION REQUIREMENT

Sir:

In response to the Office Action dated August 13, 2002, please consider the following:

REMARKS

In response to the Examiner's restriction requirement, Applicant hereby elects the invention of Group I (e.g., drawn to a method of forming a device as defined by claims 1-21), without traverse. Applicant reserves the opportunity to file a Divisional Application for the non-elected invention later.

Early, favorable prosecution on the merits is respectfully requested.

Should the Examiner find the application to be other than in condition for allowance, the Examiner is requested to contact the undersigned at the local telephone number listed below to discuss any other changes deemed necessary in a <u>telephonic or personal interview</u>.

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